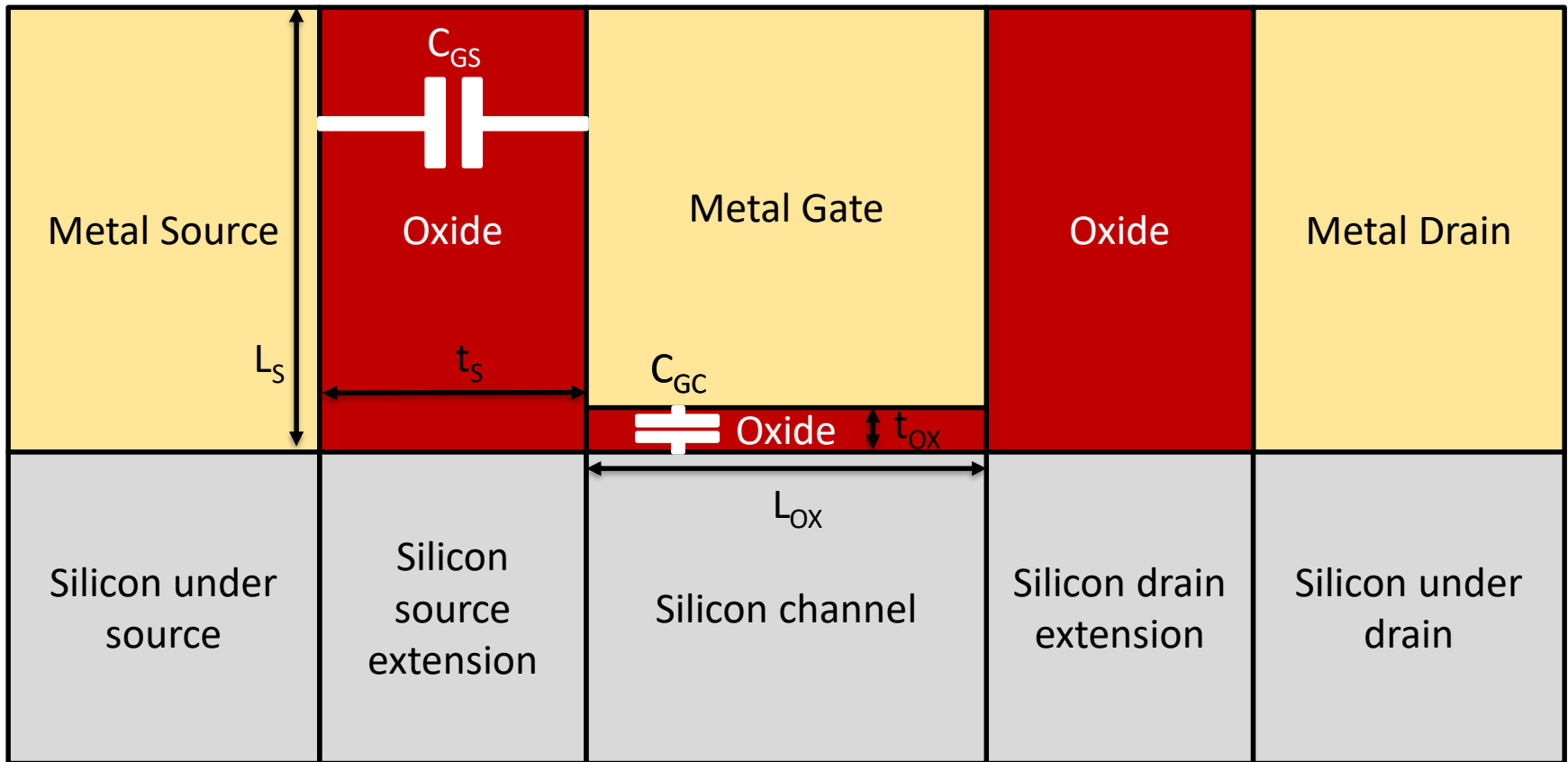


$$L_S = 50 \text{ nm}, \quad t_S = 35 \text{ nm}, \quad C_{GS} = \frac{L_S \epsilon_{OX}}{t_S} = \frac{5 \times 10^{-6} \text{ cm} \times 3.9 \times 8.854 \times 10^{-14} \text{ F/cm}}{3.5 \times 10^{-6} \text{ cm}} = 4.93 \times 10^{-13} \text{ F/cm}$$

$$L_{OX} = 35 \text{ nm}, \quad t_{OX} = 5 \text{ nm}, \quad C_{GC} = \frac{L_{OX} \epsilon_{OX}}{t_{OX}} = \frac{3.5 \times 10^{-6} \text{ cm} \times 3.9 \times 8.854 \times 10^{-14} \text{ F/cm}}{0.5 \times 10^{-6} \text{ cm}} = 2.42 \times 10^{-12} \text{ F/cm}$$

$$C_{Gate} = C_{GS} + C_{GC} = 2.91 \times 10^{-12} \text{ F/cm}$$

The input for the “normalized” C_{gs} capacitance would be “1” because this is the initial transistor



$$L_S = 50 \text{ nm}, \quad t_s = 30 \text{ nm}, \quad C_{GS} = \frac{L_S \epsilon_{OX}}{t_s} = \frac{5 \times 10^{-6} \text{ cm} \times 3.9 \times 8.854 \times 10^{-14} \text{ F/cm}}{3 \times 10^{-6} \text{ cm}} = 5.76 \times 10^{-13} \text{ F/cm}$$

$$L_{OX} = 45 \text{ nm}, \quad t_{OX} = 5 \text{ nm}, \quad C_{GC} = \frac{L_{OX} \epsilon_{OX}}{t_{OX}} = \frac{4.5 \times 10^{-6} \text{ cm} \times 3.9 \times 8.854 \times 10^{-14} \text{ F/cm}}{0.5 \times 10^{-6} \text{ cm}} = 3.11 \times 10^{-12} \text{ F/cm}$$

$$C_{Gate} = C_{GS} + C_{GC} = 3.68 \times 10^{-12} \text{ F/cm}$$

The gate capacitance for this structure has increased, so the new “normalized” C_{gs} capacitance
 = new capacitance / original capacitance = $3.68\text{e-}12/2.91\text{e-}12 = 1.265$